



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent

In re patent application of: ITANO, Mitsushi

Serial No.: 09/214,708

Filed: January 11, 1999

For: CLEANING GAS

Examiner: Winter, Gentle E.

Art Unit: 1746

Docket #: P06217US0/BAS

AMENDMENT

Commissioner for Patents
Washington, D.C.

SIR:

In response to the Office Action mailed November 21, 2002, please amend the above-identified application as follows.

IN THE CLAIMS

It will be noted that claim 11 has been amended relative to the previously provided version as shown by the marked up version thereof in **Attachment A** provided herewith. A clean version of all pending claims is provided herewith in **Attachment B**.

REMARKS

Claims 11-18 are pending in the present application. By this Amendment, Applicant has amended claim 11. Applicant respectfully submits that the present application is now in condition for allowance based on the discussion that follows.

Claims 11, 12, 14-16 and 18 were rejected under 35 U.S.C. § 102(b) as being anticipated by U.S. Patent No. 4,581,101 to Senoue et al (hereinafter "Senoue"). The Examiner alleges that Senoue discloses "an etching gas which is capable of removing the etching residue or polymer or of efficiently preventing the formation thereof" citing

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